

CLEAN METHOD FOR VAPOR DEPOSITION PROCESS

ABSTRACT OF THE DISCLOSURE

5 A method for cleaning a reaction chamber having a pedestal and a carrier ring is provided. First, the pedestal and the carrier ring are cleaned with a high pressure gas. Next, the carrier ring is moved to leave the pedestal, and a low pressure gas is provided to clean the pedestal, the carrier ring, and an area lay between the pedestal and the carrier ring. Thereafter, a full flush is performed to clean the pedestal and the carrier
10 ring.

Figure 6